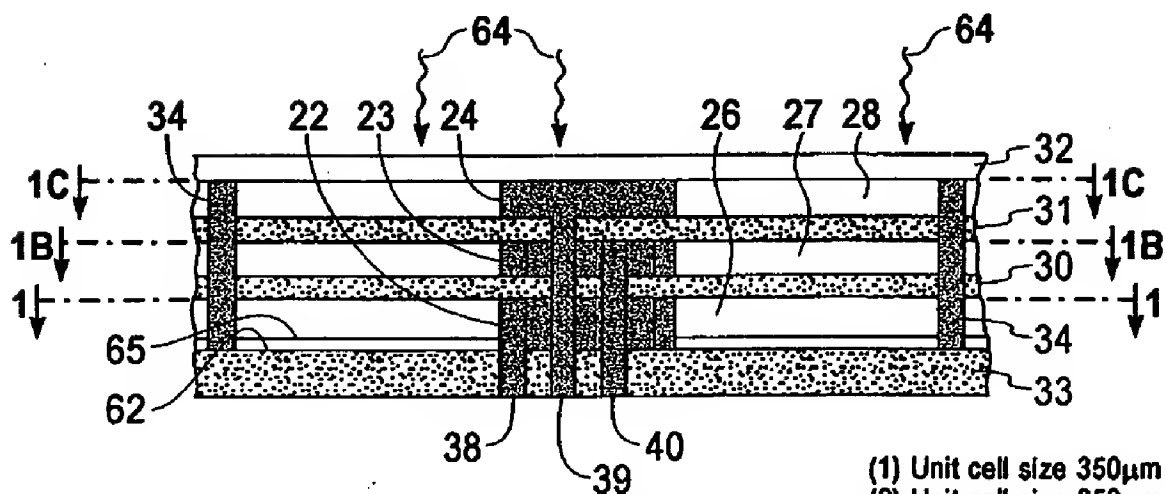
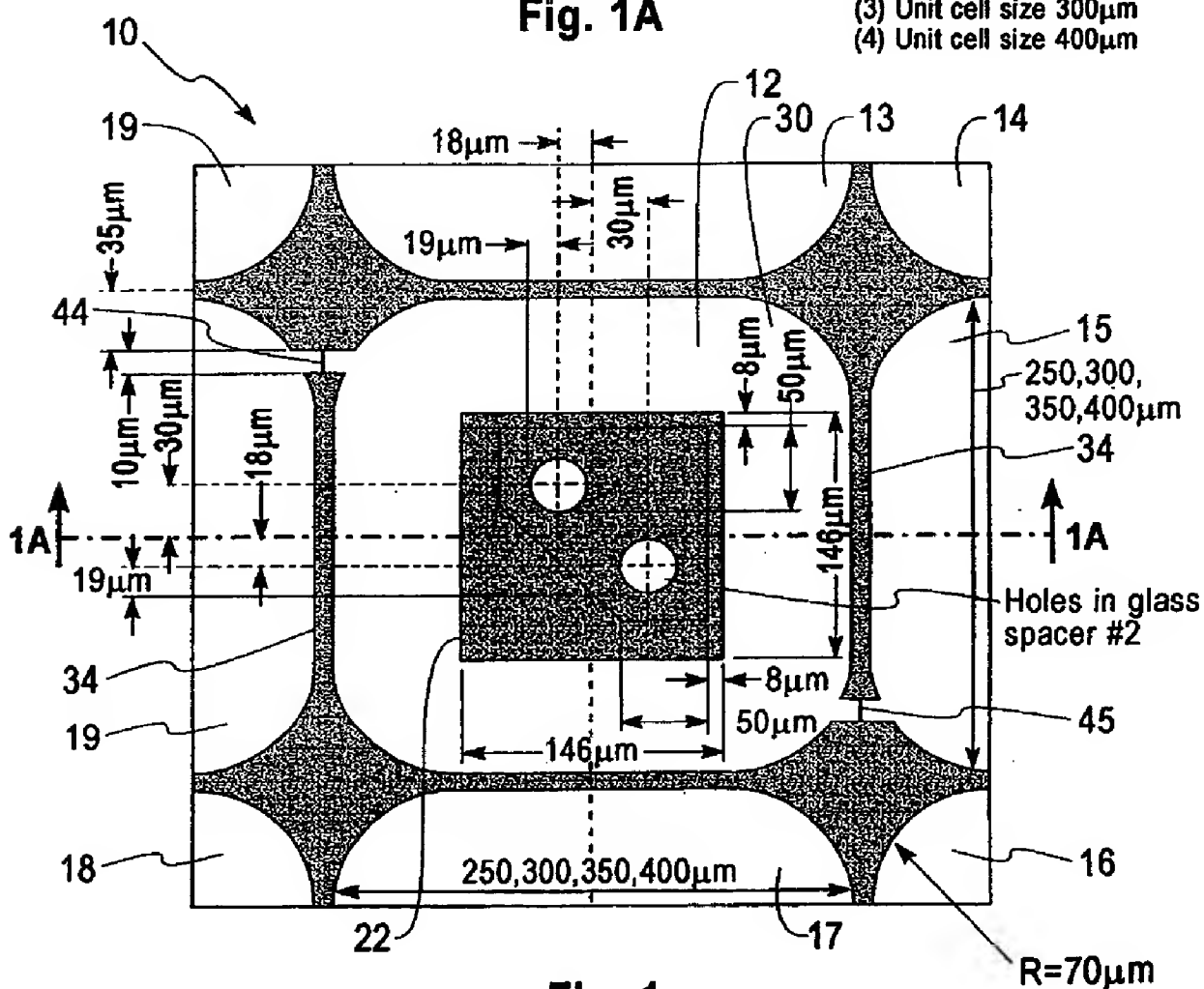


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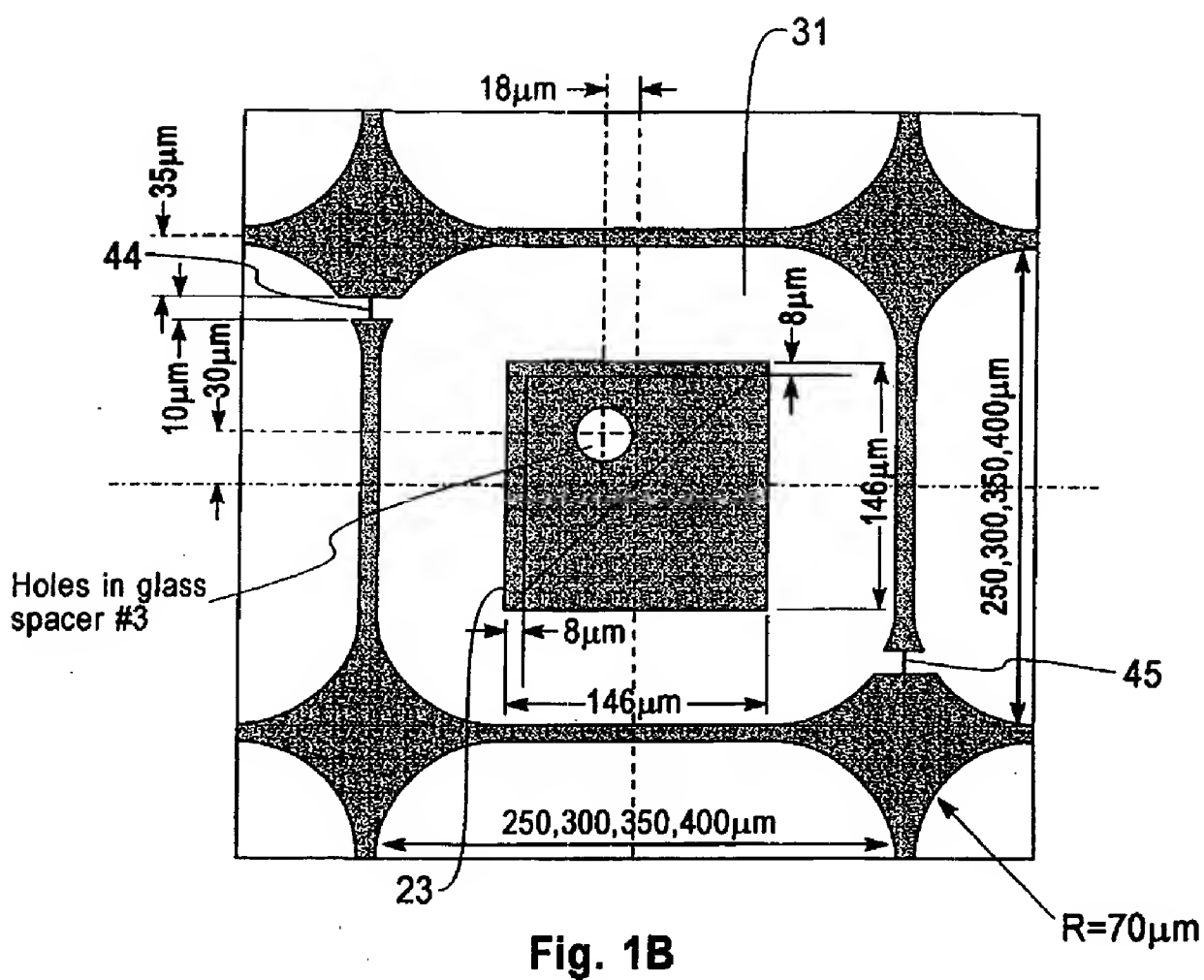
**Fig. 1A**

- (1) Unit cell size 350μm
- (2) Unit cell size 250μm
- (3) Unit cell size 300μm
- (4) Unit cell size 400μm



**Fig. 1**

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**Fig. 1B**

Received from &lt; &gt; at 4/8/02 3:28:50 PM [Eastern Daylight Time]

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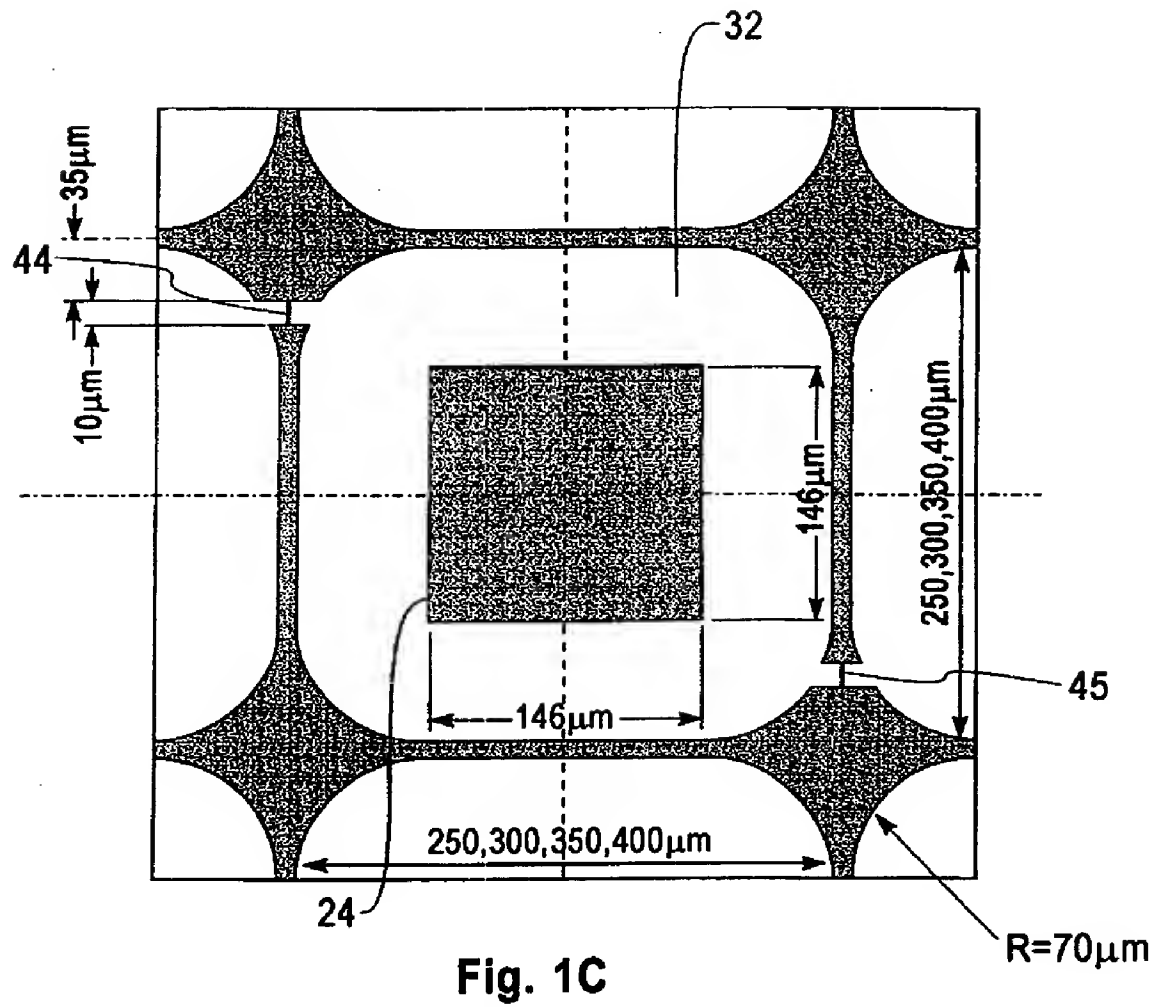
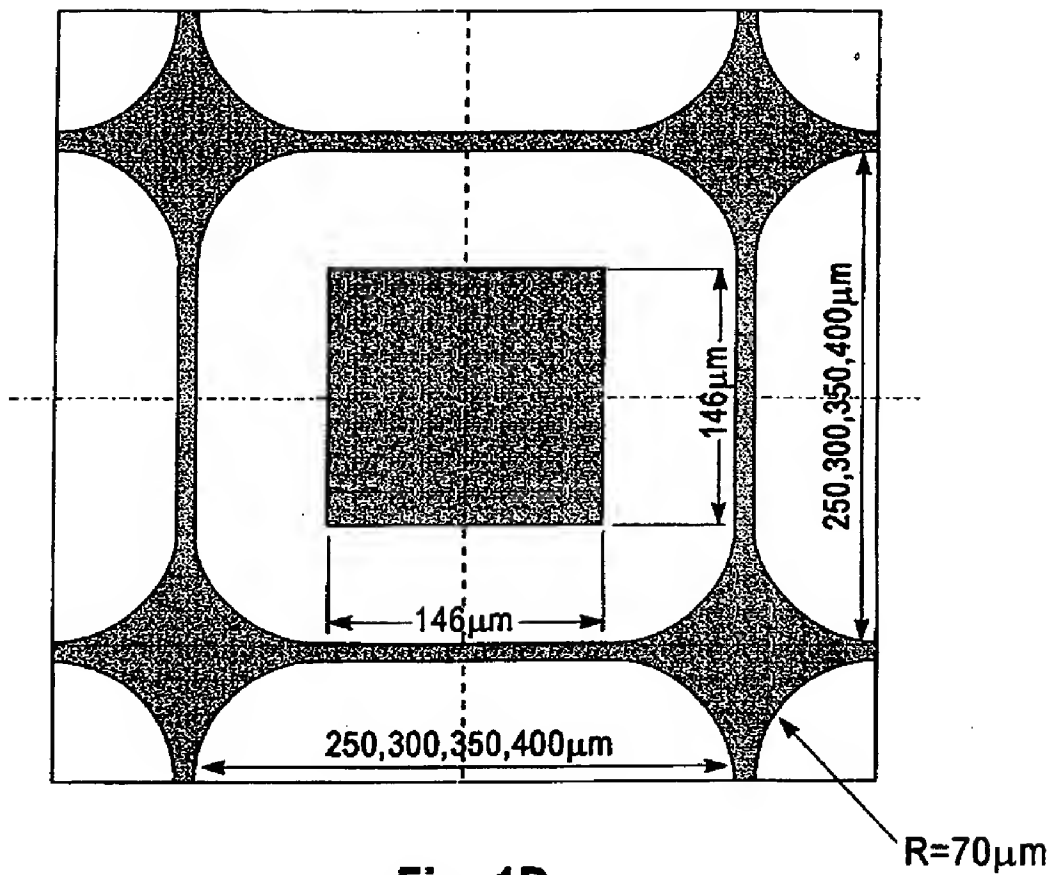


Fig. 1C

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R.M.T. YOR920000819US2

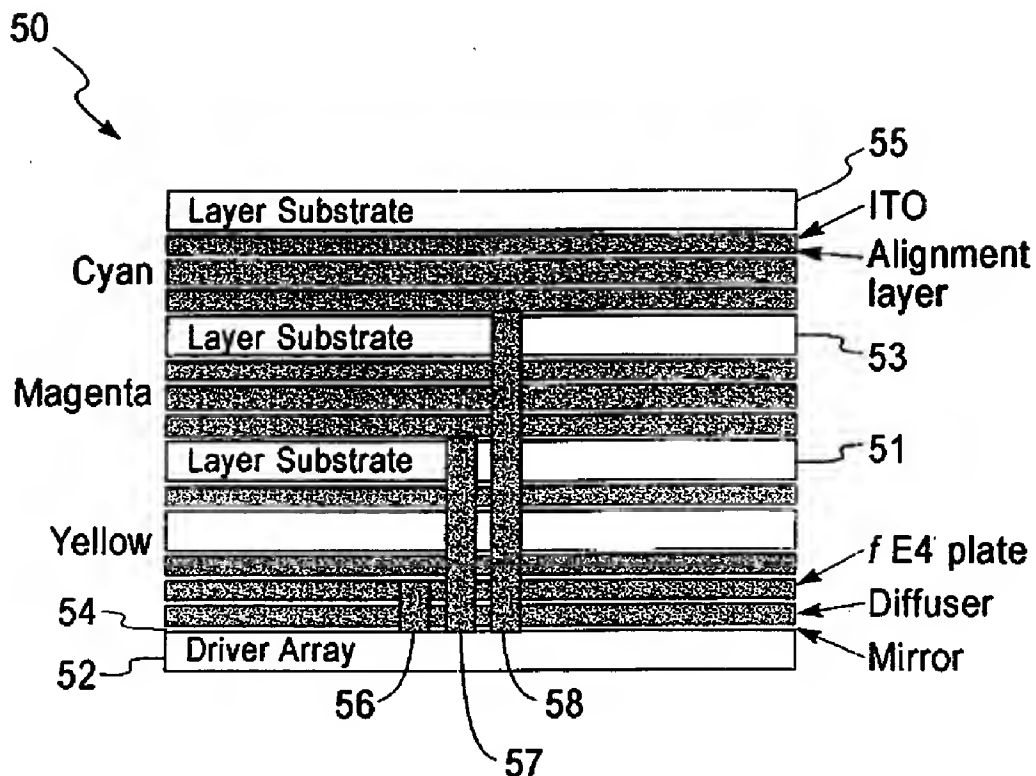


Fig. 2

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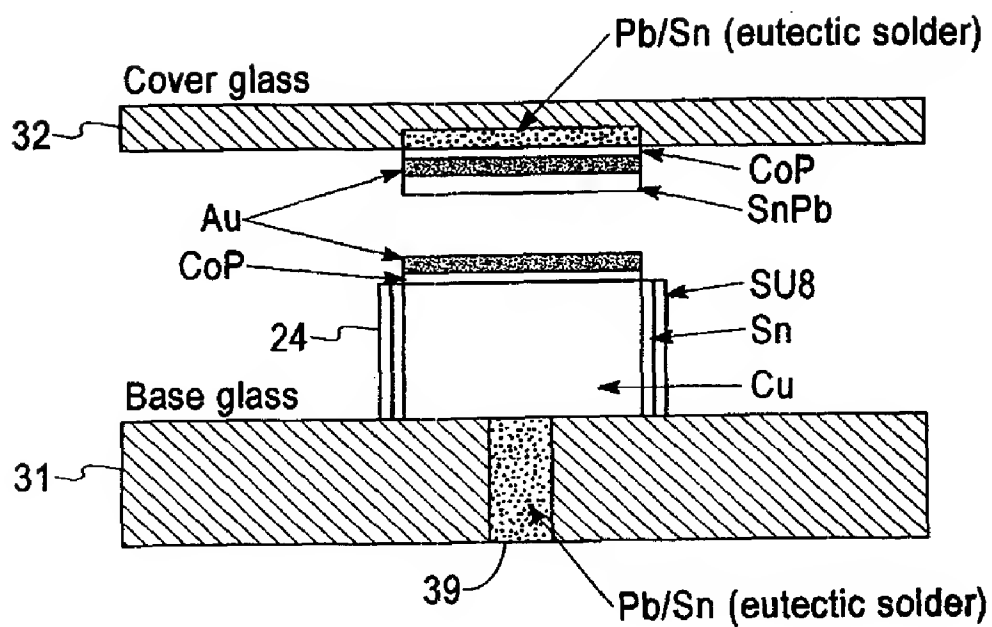


Fig. 3

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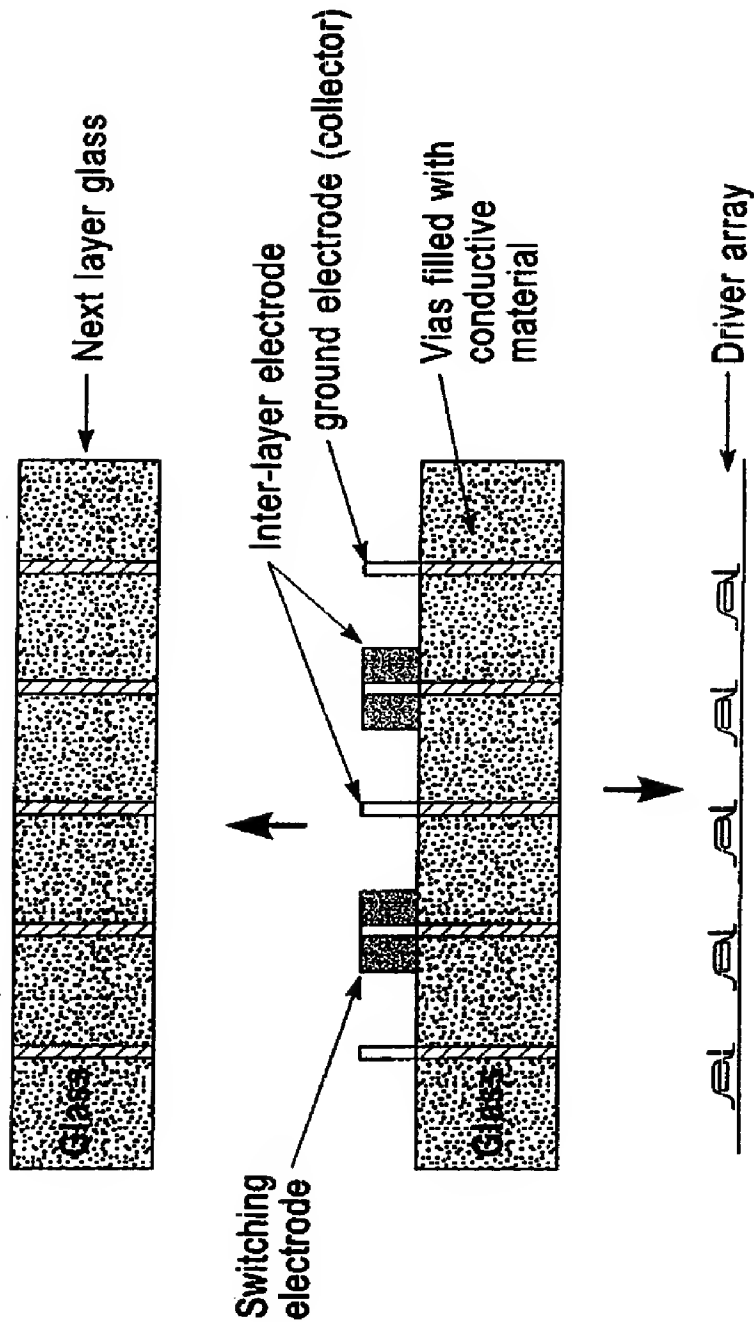
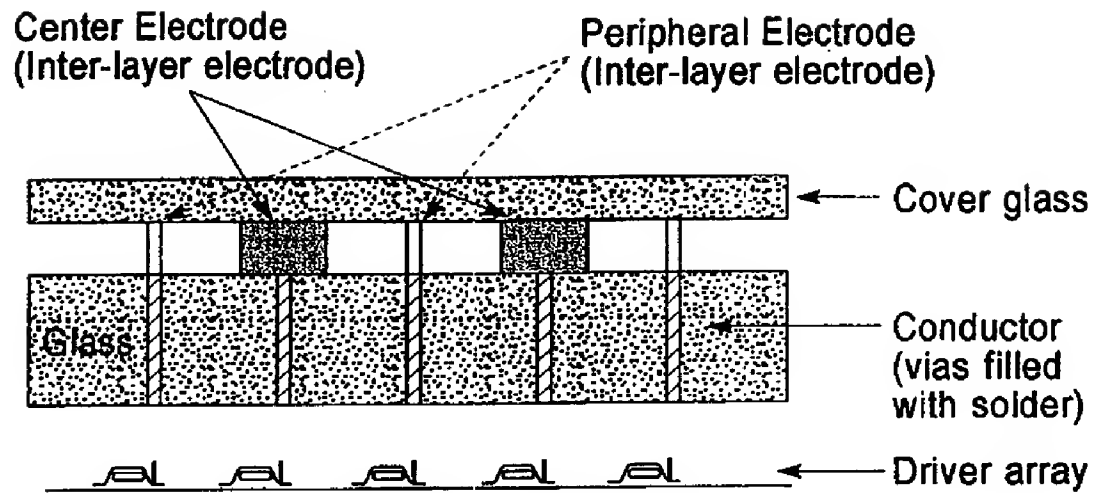


Fig. 4A

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**Fig. 4B**



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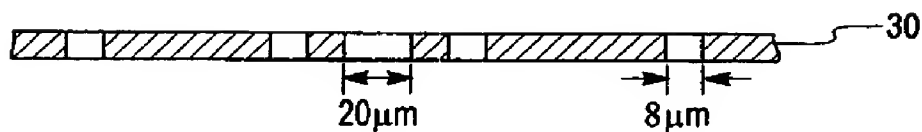


Fig. 5A

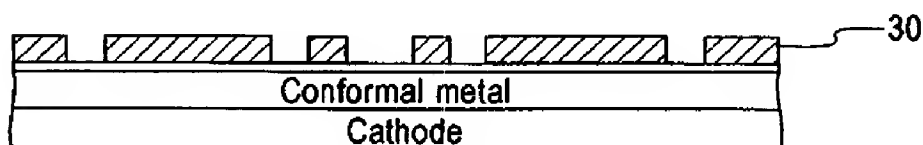


Fig. 5B

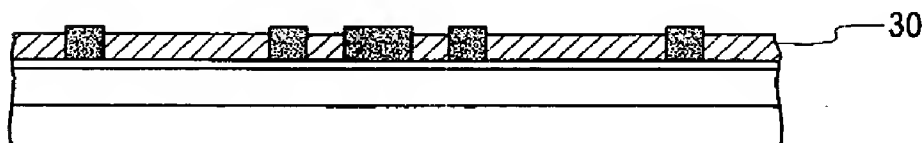


Fig. 5C

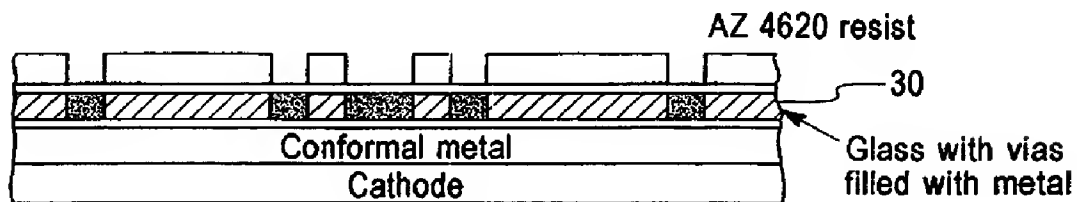
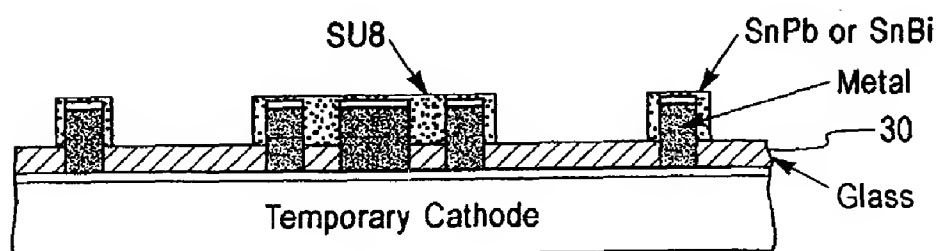


Fig. 5D

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**Fig. 5E**

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Top Cover Plate - Top View

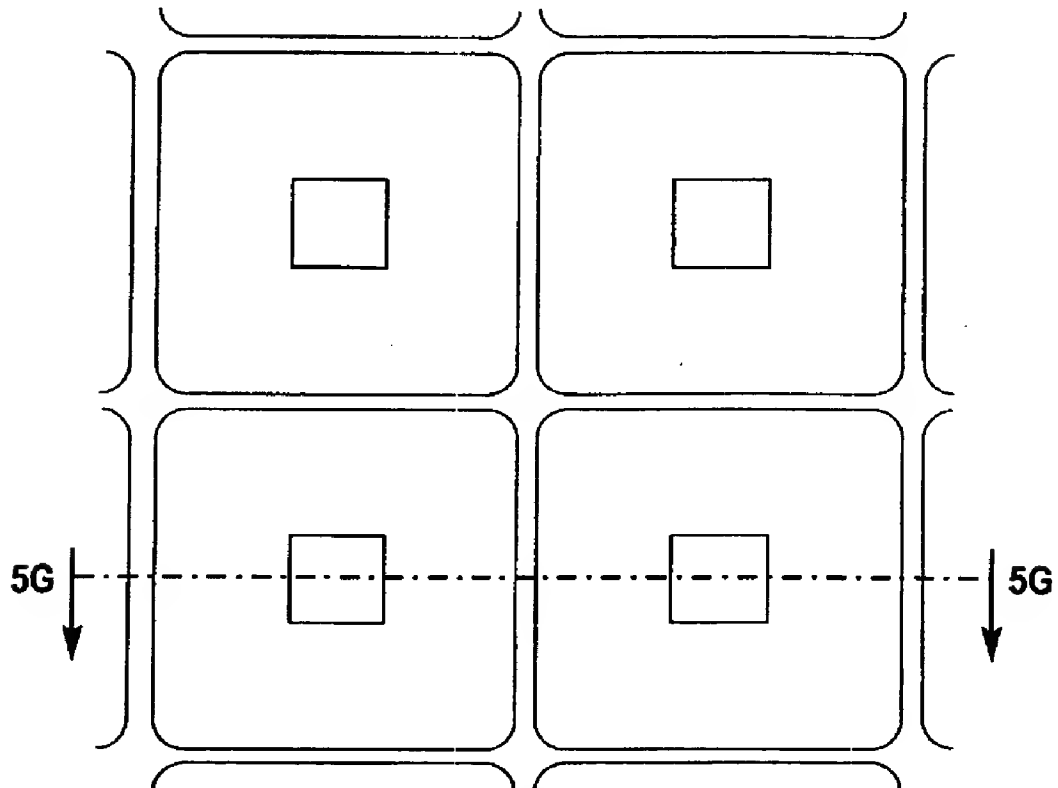


Fig. 5F



Fig. 5G

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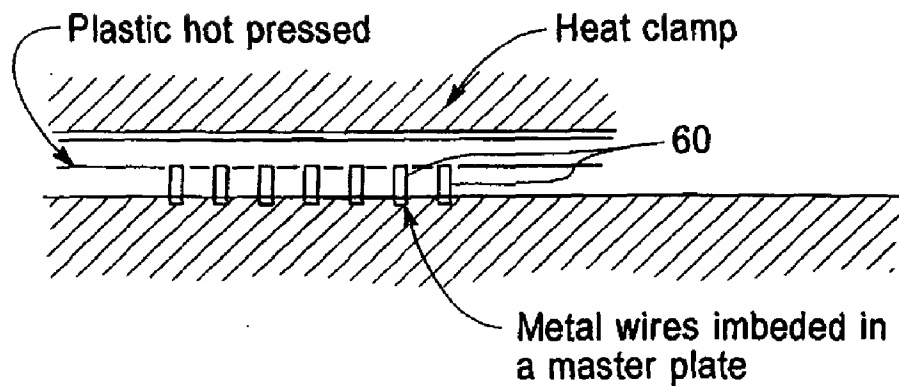


Fig. 6A

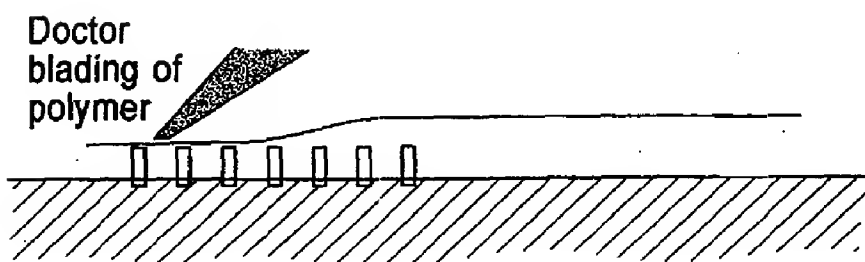


Fig. 6B

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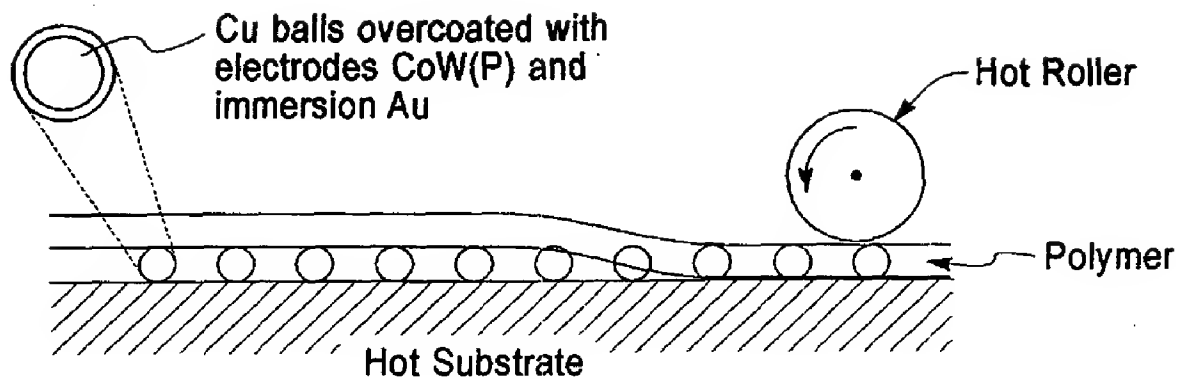


Fig 6C

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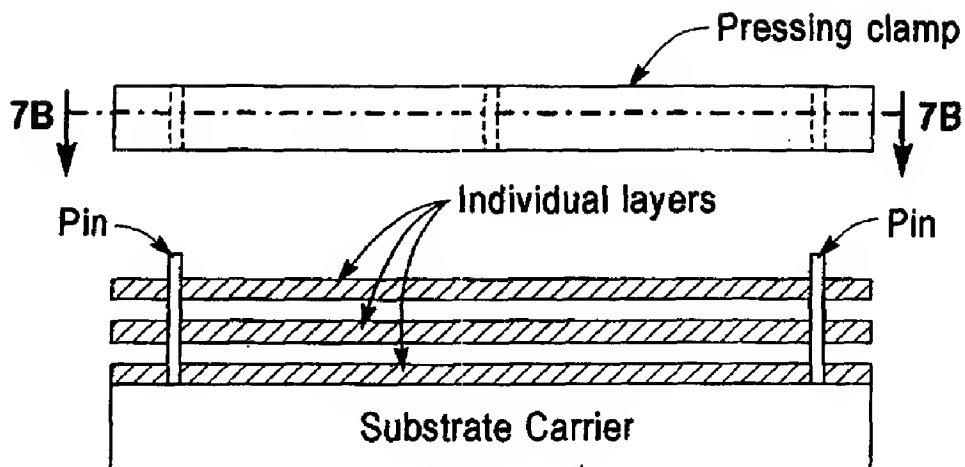


Fig. 7A

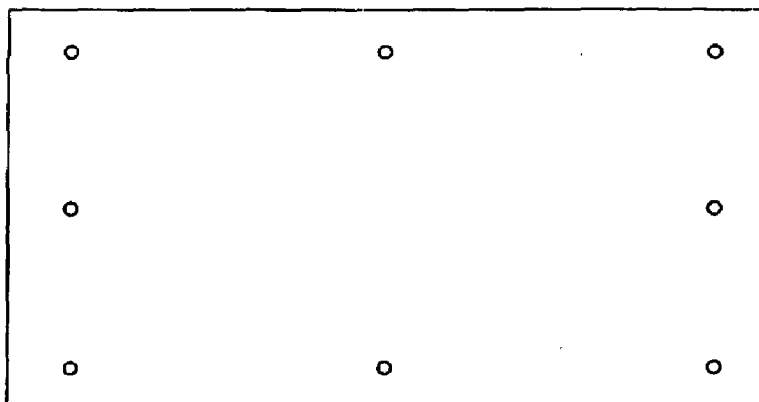


Fig. 7B

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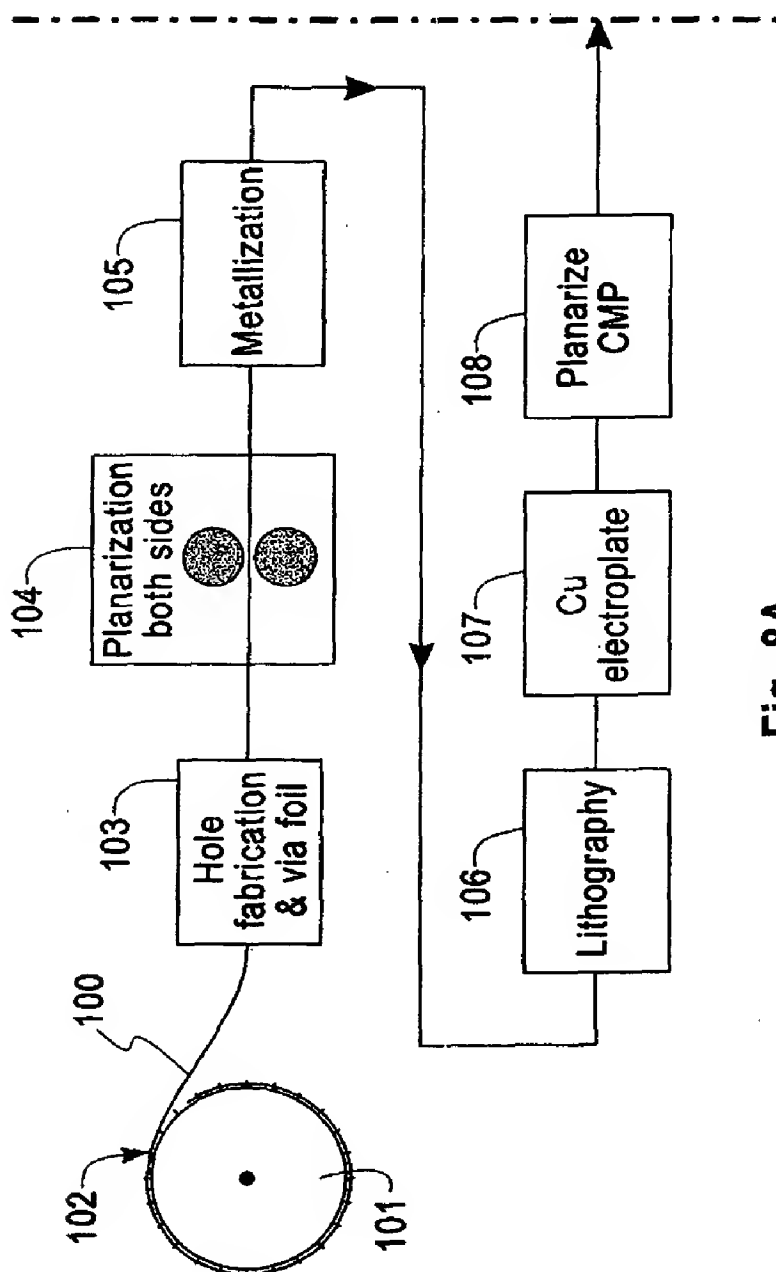


Fig. 8A



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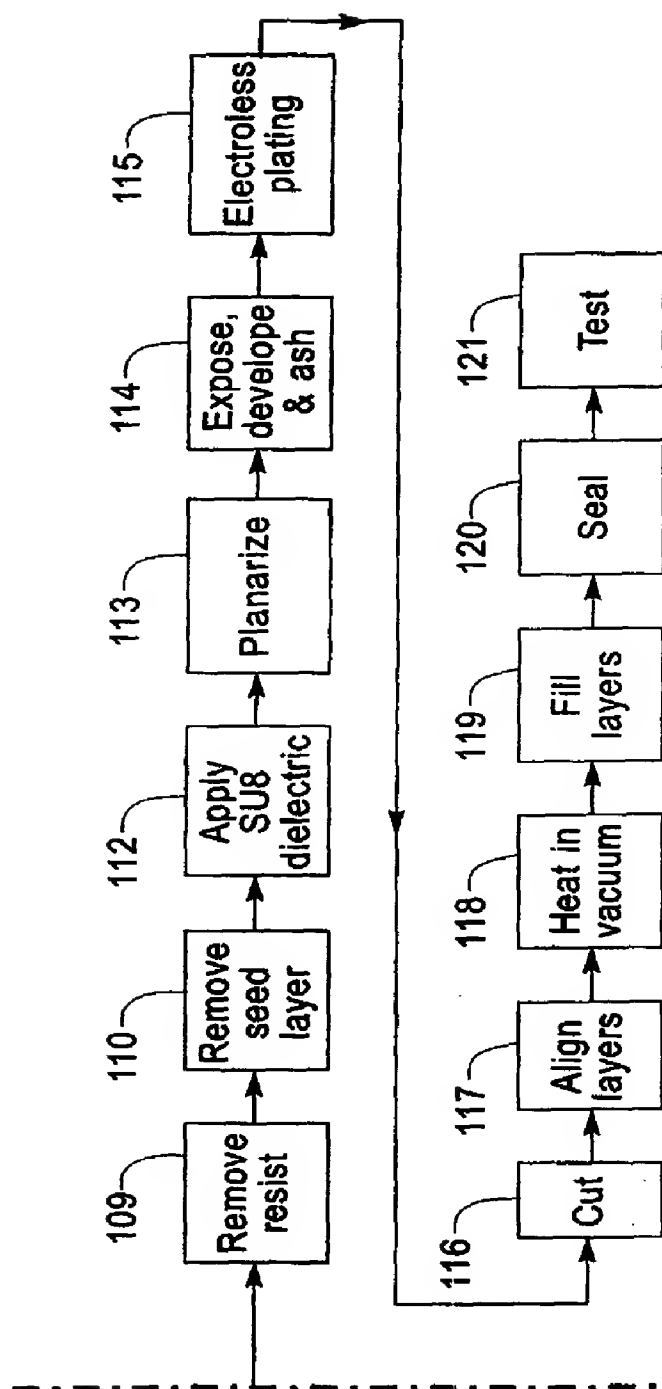


Fig. 8B





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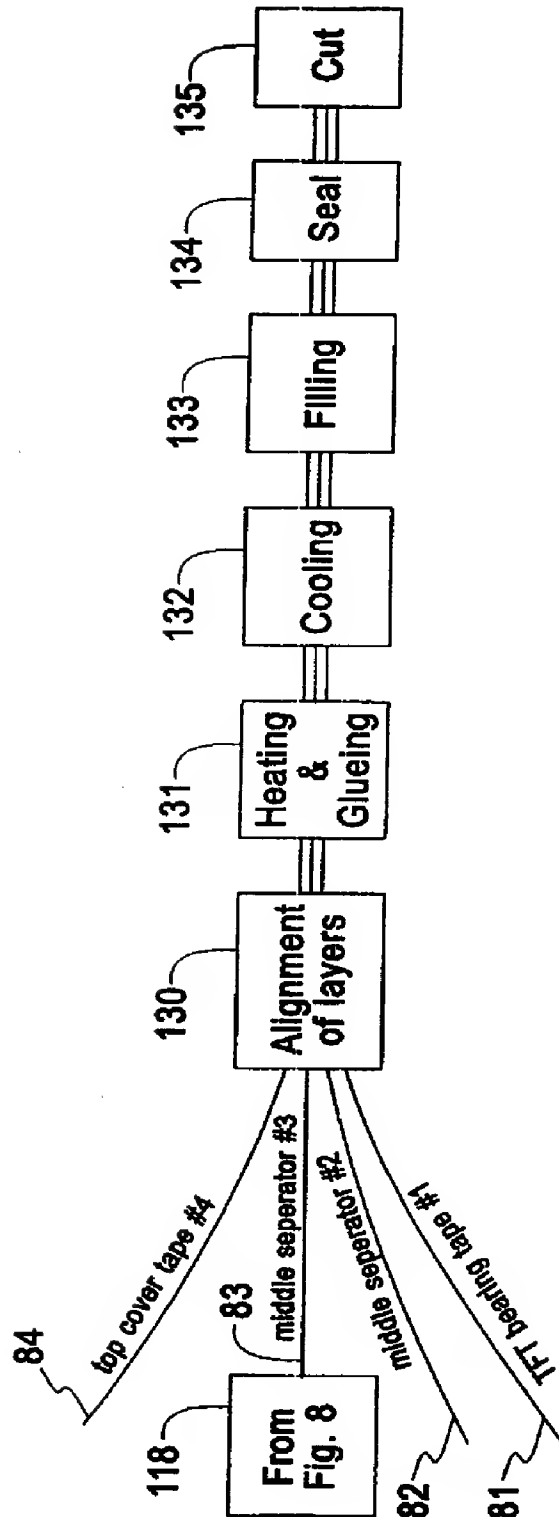


Fig. 9

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### Via making by photo etching

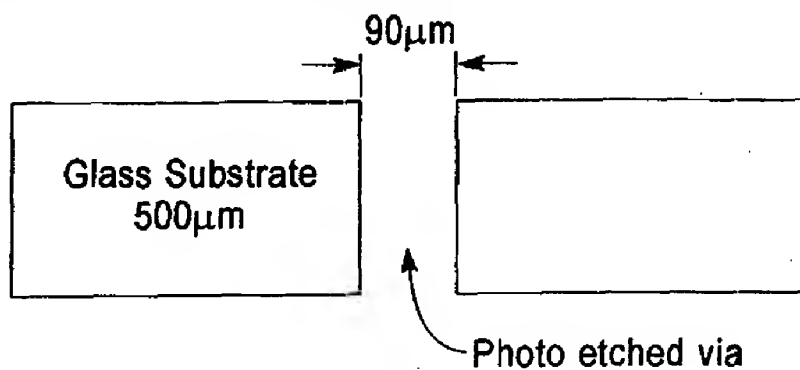


Fig. 10A

### Sputtering ITO and patterning

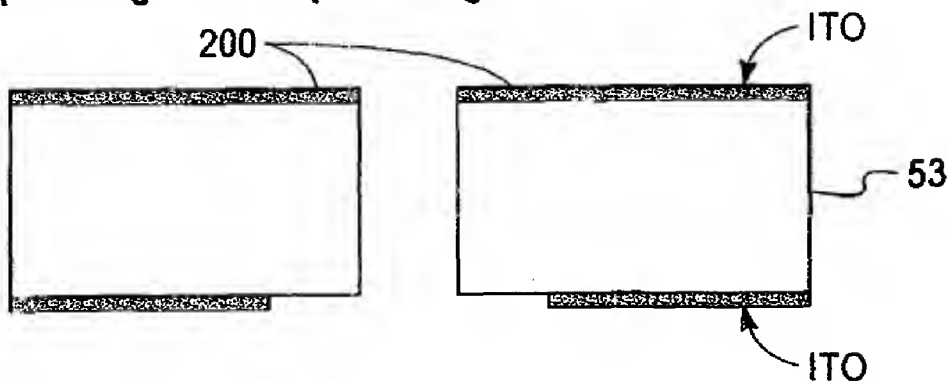
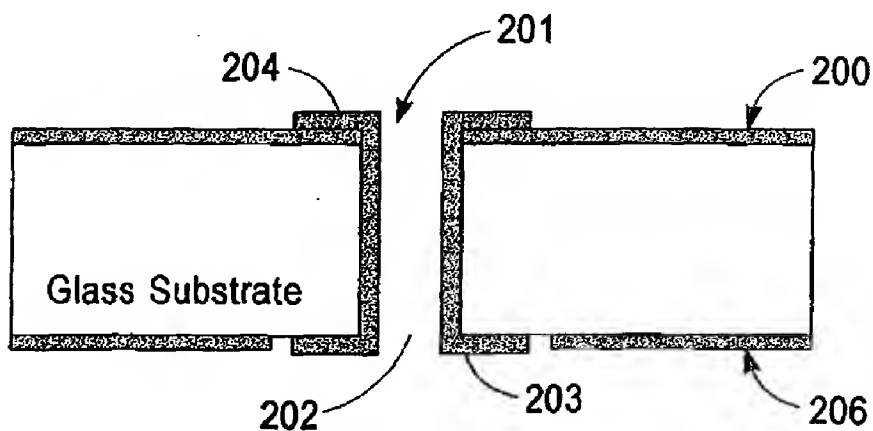


Fig. 10AA

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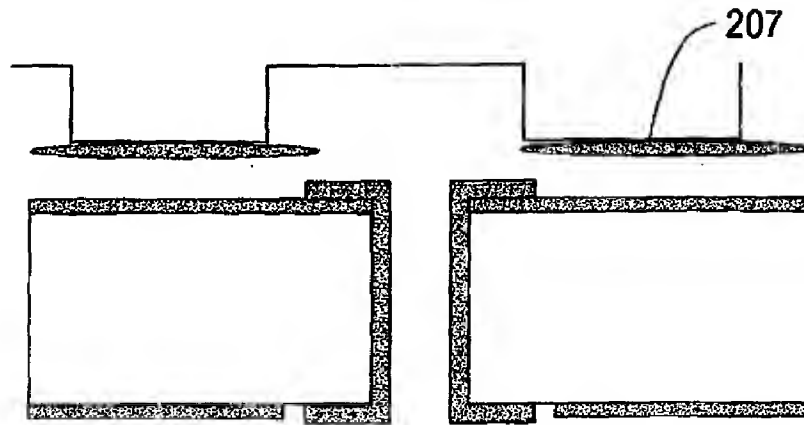
**Vertical electrode by copper plating**



**Fig. 10B**

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### Polyimide coat and patterning (Printing)



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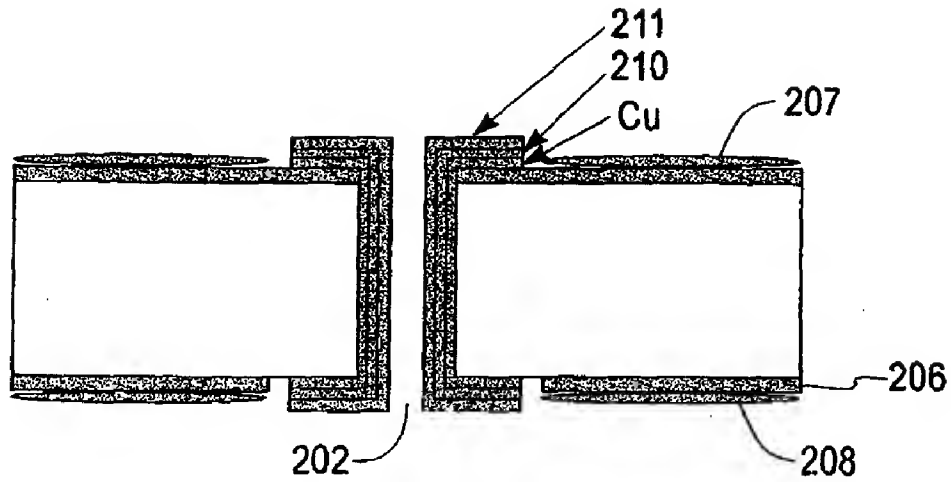


Fig. 10D

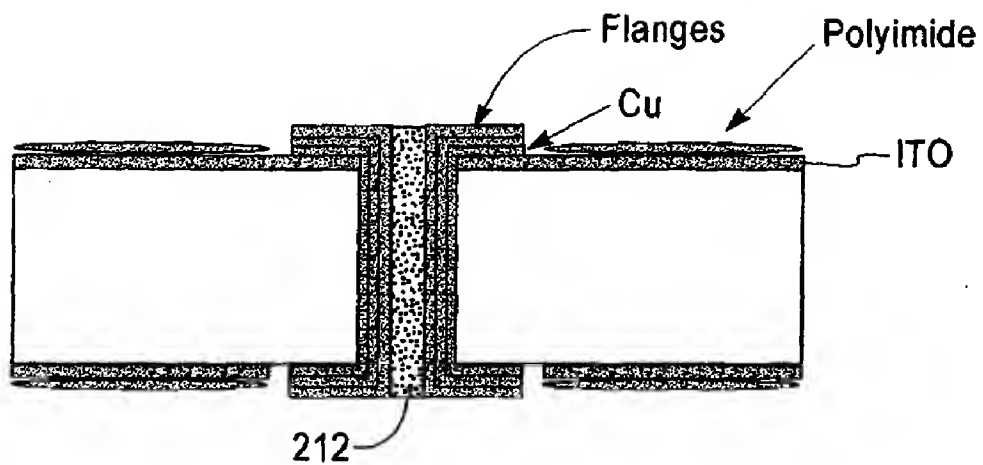


Fig. 10DD

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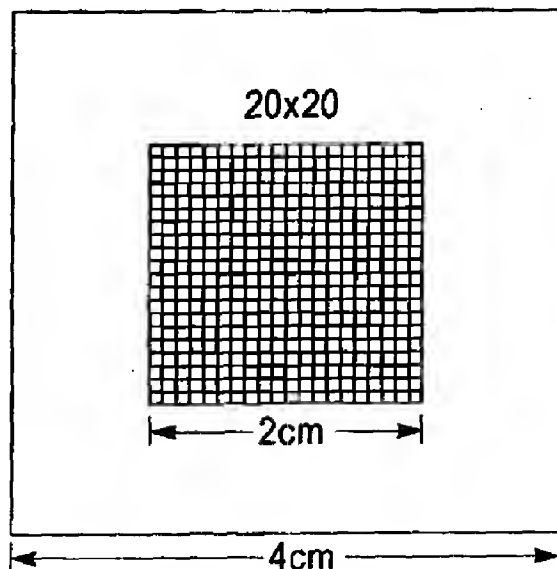
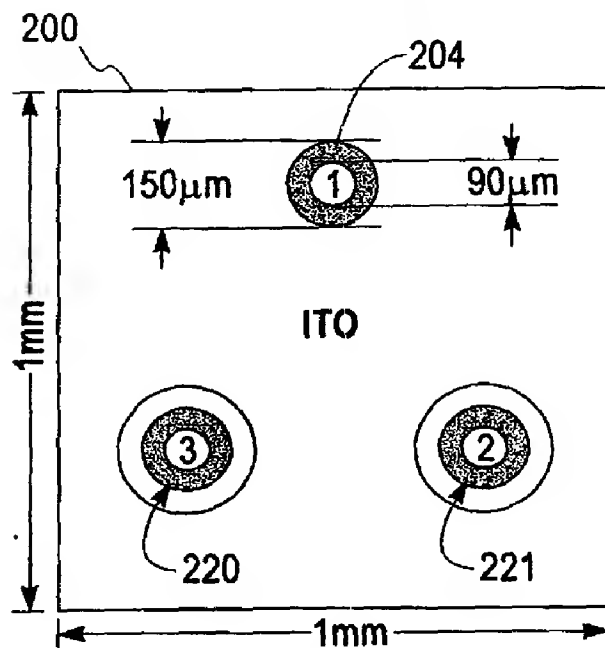


Fig. 10E



One Pixel  
Fig. 10EE

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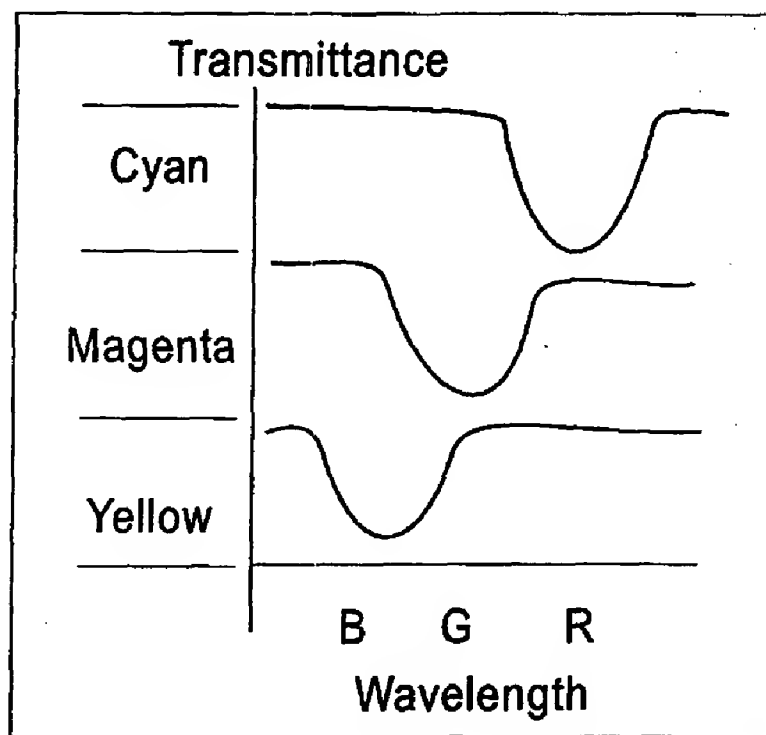


Fig. 10F

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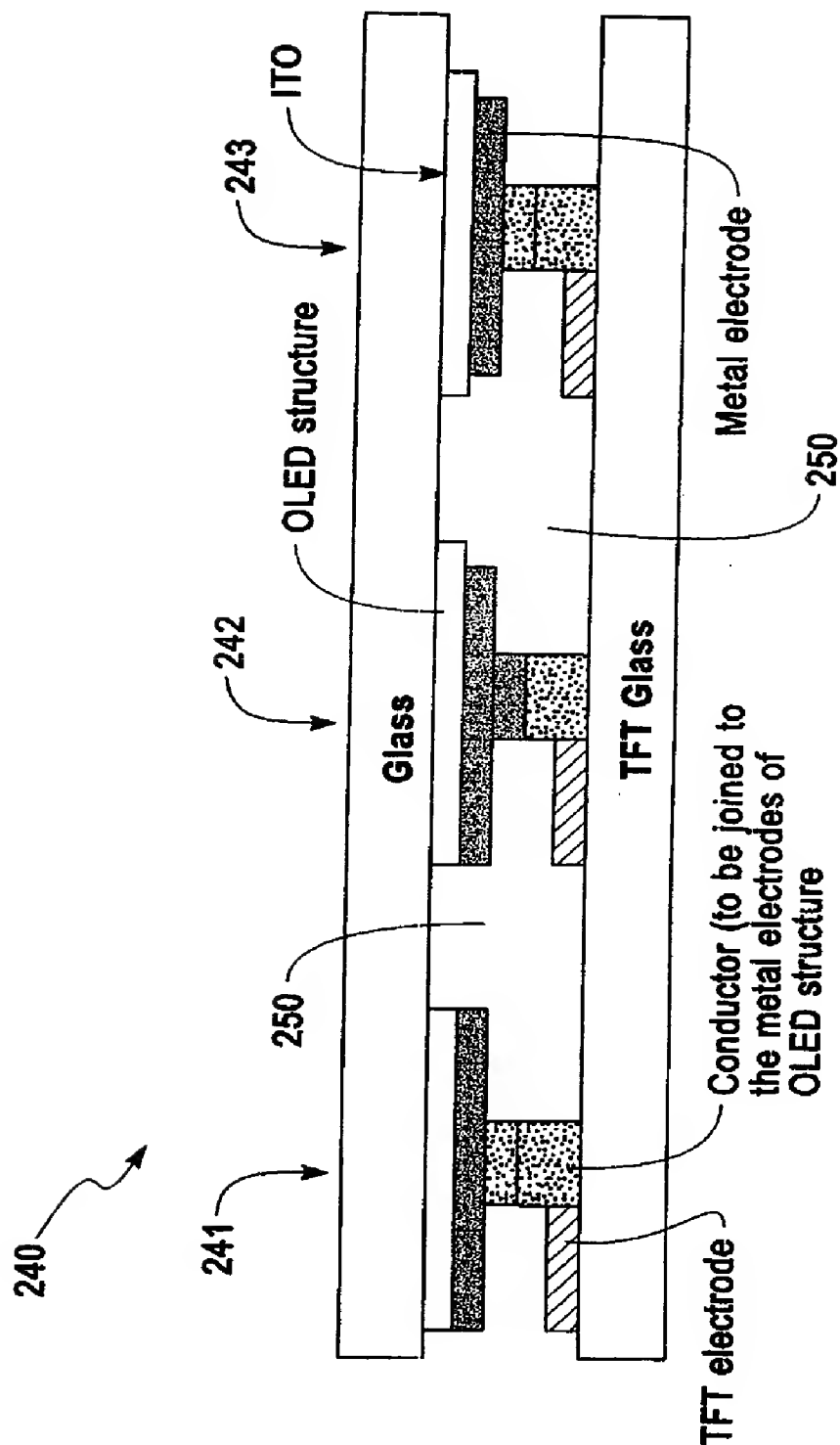


Fig. 11



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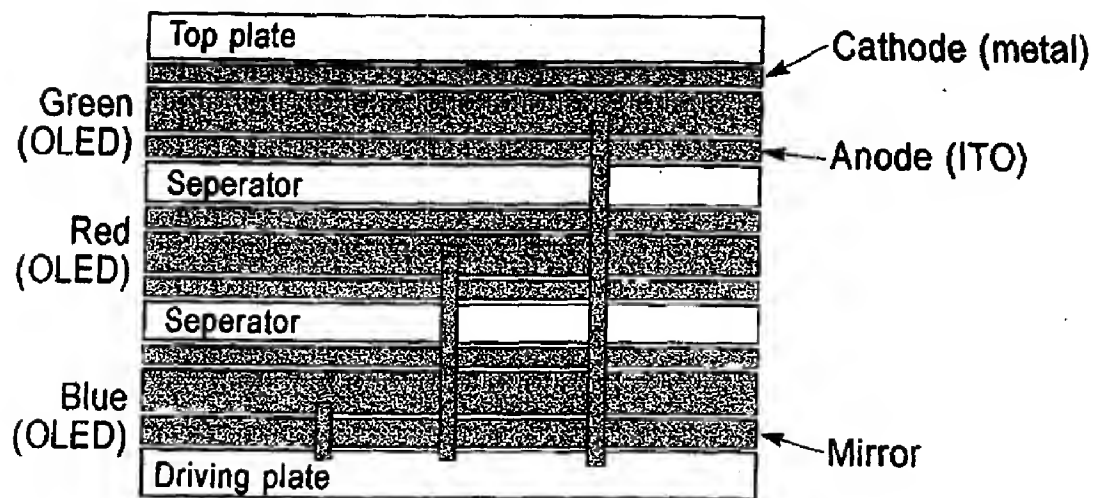


Fig. 12